

Objectives

Plan Apo EPI Series Objectives

Widely used in semiconductor manufacturing and quality inspection, electronic component and MEMS testing, metal material analysis, precision molds and mechanical parts

- Apochromatic correction
- Flat field design
- 95mm infinite conjugate parfocal architecture
- High resolution and long working distance
- EPI episcopic bright field optimization



One Platform Many Possibilities

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Explore Series

Model	R	NA	±D.F	WD
VL Plan Apo EPI 50X	0.29um	0.95	0.3um	0.35mm
VL Plan Apo EPI 100X	0.29um	0.95	0.3um	0.35mm

 Get in touch with our team to explore configurations, request a quote, or learn more about customized solutions tailored to your needs.

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